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 INFORMATION DISCLOSURE
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 FILING DATE
October 30, 2000

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(Use several sheets if necessary)

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

0.1	S. Creutz, P. Teyssie, R. Jerome, <u>Living Anionic Homopolymerization and Block Copolymerization of (Dimethylamino)ethyl Methacrylate</u> , <u>Macromolecules</u> , 30, pg. 6-9 (1997)
0.1	P. Chaumont, D. Colombani, L. Boiteau, J.P. Lamps, M. Zink, C.P.R. Nair, and P. Charmot, <u>Free Radical Synthesis of Functional Polymers Involving Addition-Fragmentation Reactions</u> , American Chemical Society (Chapter 22, pg. 362-376) (1998)
0.1	J. Chiefari, Y. K. Chong, F. Ercole, J. Krstina, J. Jeffrey, T. Le, R. Mayadunne, G. Meijs, C. Moad, G. Moad, E. Rizzardo, S. Thang, <u>Living Free-Radical Polymerization by Reversible Addition-Fragmentation Chain Transfer: The RAFT Process</u> , <u>Macromolecules</u> , 31, pg. 5559-5562 (1998)
0.1	A. Sebenik, <u>Living Free-Radical Block Copolymerization Using Nitro-Iniferters</u> , <u>Prog. Polym. Sci.</u> Vol. 23, pg 875-917 (1998)
0.1	J. Krstina, C. Moad, G. Moad, E. Rizzardo, <u>A New Form of Controlled Growth Free Radical Polymerization</u> <u>Macromol. Symp.</u> 111, pg. 13-23 (1996)
0.1	S. Sandler, W. Karo, <u>Organic Chemistry, Polymer Syntheses</u> Vol. II, Academic Press N.Y., Chapter 7, <u>Poly(Vinyl Ethers)</u> , pgs. 214-231 (1974)
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0.1	X. Zhang, K. Matyjaszewski, <u>Synthesis of Well Defined Amphiphilic Block Copolymers with 2 Dimethylaminoethyl Methacrylate by Controlled Radical Polymerization</u> , <u>Macromolecules</u> 32, 1763-1766 (1999)
0.1	N. Hoogeveen, M. Sohen Stuart, G. Fleer, <u>Novel Water-Soluble Block CoPolymers of Dimethylaminoethyl Methacrylate and Dihydroxypropyl Methacrylate</u> , <u>Macromolecules Chem. Phys.</u> , 197, pg. 2553-2564 (1996)

EXAMINER

Olga Asinowsky

DATE CONSIDERED

June 19, 2002

EXAMINER: Initial if citation is considered, draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
O.I.P.E. O.A. NOV 16 2001 PATENT & TRADEMARK OFFICE		4	5	2	8	1	1	1	07/85	Su		
		5	3	3	8	5	4	1	08/94	Matz et al		

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
												YES	NO
O.A.		9	8	0	1	4	7	8	01/98	WO		X	
C.A.		5	3	1	1	1	9	4A2	11/93	JP		Abstract and Computer	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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